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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/506,558	09/01/2004	Young Yul Kim	61282.00015	1334	
30256 7:	590 10/10/2006	10/10/2006 EXAMINER			
SQUIRE, SANDERS & DEMPSEY L.L.P 600 HANSEN WAY			CROWELL, ANNA M		
PALO ALTO, CA 94304-1043			ART UNIT	PAPER NUMBER	
,			1763		
		·	DATE MAILED: 10/10/2006		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)		
	10/506,558	KIM, YOUNG YUL		
Office Action Summary	Examiner	Art Unit		
	Michelle Crowell	1763		
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the c	orrespondence address		
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA  - Extensions of time may be available under the provisions of 37 CFR 1:13 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period v  - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tim will apply and will expire SIX (6) MONTHS from , cause the application to become ABANDONE	Lely filed the mailing date of this communication. O (35 U.S.C. § 133).		
Status				
1) Responsive to communication(s) filed on 01 Section 2a) This action is FINAL.  2b) This 3) Since this application is in condition for allower closed in accordance with the practice under Example 25.	action is non-final.			
Disposition of Claims				
4)  Claim(s) 1 and 2 is/are pending in the application 4a) Of the above claim(s) is/are withdraw 5)  Claim(s) is/are allowed.  6)  Claim(s) 1 and 2 is/are rejected.  7)  Claim(s) is/are objected to.  8)  Claim(s) are subject to restriction and/or are subject to restriction and/or are subject to by the Examine 10)  The specification is objected to by the Examine 10)  The drawing(s) filed on 01 September 2004 is/a Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11)  The oath or declaration is objected to by the Examine 11)  The oath or declaration is objected to by the Examine 110  The oath or declaration is objected to by the Examine 110  The oath or declaration is objected to by the Examine 110  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath or declaration is objected to by the Examine 111  The oath of	wn from consideration.  r election requirement.  r.  are: a)⊠ accepted or b)□ object drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	37 CFR 1.85(a). ected to. See 37 CFR 1.121(d).		
Priority under 35 U.S.C. § 119	·			
<ul> <li>12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).</li> <li>a) All b) Some * c) None of:</li> <li>1. Certified copies of the priority documents have been received.</li> <li>2. Certified copies of the priority documents have been received in Application No.</li> <li>3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).</li> <li>* See the attached detailed Office action for a list of the certified copies not received.</li> </ul>				
Attachment(s)  Notice of References Cited (PTO-892)  Notice of Draftsperson's Patent Drawing Review (PTO-948)  Information Disclosure Statement(s) (PTO/SB/08)  Paper No(s)/Mail Date 09/04 & 01/05.	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal Pa	te		

#### **DETAILED ACTION**

### Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claim 1 is rejected under 35 U.S.C. 102(b) as being anticipated by Imafuku et al. (U.S. 6,074, 518).

Referring to Figure 6 and column 10, lines 9-24, Imafuku et al. discloses an electrode for dry etching a wafer, the electrode comprising a first electrode and a second electrode, the first electrode including a first flat plate 21 and a ring-shaped first protrusion 27 corresponding to one surface of the edge of a wafer, and the second electrode including a second flat plate 5 and a ring-shaped second protrusion 66 corresponding to the other surface of the edge of the wafer, wherein the first protrusion and the second protrusion are the same size.

With respect to the limitation, "for removing foreign materials from the edge of the wafer by plasma", it should be noted that this is considered a process limitation and since the invention is directed towards an apparatus such a limitation is considered intended use.

Therefore, a recitation of the intended use of the claimed invention must result in a structural difference between the claimed invention and the prior art in order to patentably distinguish the claimed invention from the prior art. If the prior art structure is capable of performing the intended use, then it meets the claim. Thus, the apparatus of Imafuku et al. is capable of performing the claimed removing foreign materials from the edge of the wafer by plasma

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#### Claim Rejections - 35 USC § 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claim 2 is rejected under 35 U.S.C. 103(a) as being unpatentable over Imafuku et al. (U.S. 6,074, 518) in view of Ohmi (U.S. 5,272,417).

The teachings of Imafuku et al. have been discussed above.

Imafuku et al. fail to teach that an insulating layer is deposited on the upper surface of the first electrode

Referring to column 6, lines 33-43, Ohmi teaches a dry etching apparatus wherein an insulating layer 101 is deposited on the upper surface of the first electrode 102 in order to prevent the first electrode from being etched by plasma. Thus, it would have been obvious to one of ordinary skill in the art at the time of the invention to provide the upper surface of the first electrode which is inside the first protrusion of Imafuku et al. with an insulating layer as taught by Ohmi since this would prevent the first electrode from being etched by plasma.

## Conclusion

5. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Itoh'947, Nam et al.'554, and Morita et al.'896 teach an electrode with a protrusion.

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Michelle Crowell whose telephone number is (571) 272-1432. The examiner can normally be reached on M-F (9:30 -6:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Michelle Crowell
Patent Examiner
Art Unit 1763

Parviz Hassanzadeh Supervisory Patent Examiner Art Unit 1763